

Search Notes

Application/Control No.

10/817,567

Examiner

D. Rutledge

Applicant(s)/Patent under
Reexamination

LIN ET AL.

Art Unit

2851

SEARCHED

Class	Subclass	Date	Examiner
396	604, 611 ,626	3/19/2005	DR
134	3,32,157	3/19/2005	DR
118	52	3/19/2005	DR
118	319-321	3/19/2005	DR

INTERFERENCE SEARCHED

Class	Subclass	Date	Examiner
396	604,611	3/19/3005	DR
396	626	3/19/2005	DR
118	52,319	3/19/2005	DR
134	32, 157	3/19/2005	DR

**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
develop\$3 near3 (wafer or substrate); rotat\$3 near3 (wafer or substrate); (wash\$3 or rins\$3) near4 (substrate or wafer)	3/19/2005	DR
(front or upper or top or patterned) near2 (surface or side); (back or rear or reverse) near2 (side or surface); (stop\$4 or	3/19/2005	DR
terminat\$3 or end\$3 or discontinu\$4) near3 (wash\$3 or rins\$3) near4 (rear or back or reverse)	3/19/2005	DR